

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Inventor:

Tatau NISHINAGA

Group Art Unit: 1765

Appln. No.:

09/511,912

Examiner: M. Anderson

Filed:

February 23, 2000

For:

A METHOD FOR FORMING A SINGLE CRYSTALLINE FILM

SUPPLEMENTAL AMENDMENT UNDER 37 CFR § 1.111

Assistant Commissioner of Patents Washington, D.C. 20231

Sir:

Supplemental to the Amendment filed December 12, 2002, the Applicant requests further amendment of the above-captioned application as follows:

IN THE CLAIMS:

Kindly add the following new claims.

--20. The method of claim 1, wherein:

the single crystalline substrate is formed from one of the group of Si, GaAs, ZnSe, SrTiO3, and sapphire; and

the single crystalline film is formed from one of the group of Si, GaAs, Ga_{1-x}Al_xAs, ZnSe, ZnS, CdTe, ZnS_{1-x}Se_x, and YBCO.

21. The method of claim 1, wherein:

the single crystalline substrate is formed from one of the group of Si, GaAs, ZnSe, and SrTiO₃; and

#21/29 Medic 12/27/20